

LITHOGRAPHIC APPARATUS AND DEVICE MANUFACTURING METHOD

ABSTRACT

A lithographic apparatus and method are used to pattern a substrate. The system and method includes an illumination system for supplying a projection beam of radiation, an array of individually controllable elements for imparting the projection beam with a pattern in its cross-section, and a substrate table for supporting the substrate during an exposure operation. A projection system projects the patterned beam onto a target portion of the substrate. A control system sends a control signal for setting each said individually controllable elements to a desired state. A compensation device for adjusting the control signal applied to a first individually controllable element based on the control signal to be applied to at least one other individually controllable element. This can be done to reduce image degradation arising from cross-talk between individually controllable elements.

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